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**PATENT
CH920010003US1
(Corrected version)**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of Applicants:

Date: January 17, 2005

Bietsch, et al.

Group Art Unit: 1751

Serial No.: 10/081,860

Examiner: LynetteT Umez Eronini

Filed: February 22, 2002

Docket No.: CH920010003US1

For: *SELECTIVE ETCHING OF SUBSTRATES WITH CONTROL OF THE ETCH PROFILE*

Assistant Commissioner for Patents
Post Office Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Official Action dated May 2, 2005, please amend the above-identified application as set forth in the Appendix attached hereto.

IN THE CLAIMS:

Cancel all Claims except for Claim 1 which now embodies the substance of Claims 11 and 12.

REMARKS

It is submitted that the claims as amended in the instant response will place the claims in condition for allowance.